

## **Licensing Process**

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Computers and Nuclear Energy
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# Licensing under Part 50 vs. Licensing under Part 52

Same – most requirements

 Different – applications, process, timing, and finality



#### Required for Licensing

- Applicant Qualifications
- Design Acceptability
- Environmental Impacts
- Operational Programs
- Site Safety
- Verification with Inspections, Tests, Analyses and Acceptance Criteria (ITAAC)



### Licensing Steps under Part 50

- LWA under 10 CFR 50.10
- Construction Permit 10 CFR 50.35(a)
- Byproduct Material under Part 30
- Source Material under Part 40
- Special Nuclear Material under Part 70
- Operating License 10 CFR 50.57



### Part 50 Licensing Process

- Construction Permit 50.34(a)
  - Preliminary Design
  - Site Safety
  - Environmental Impacts
  - Mandatory Hearing
- Operating License 50.34(b)
  - Final Design
  - Operational Programs
  - Emergency Preparedness
  - Optional Hearing

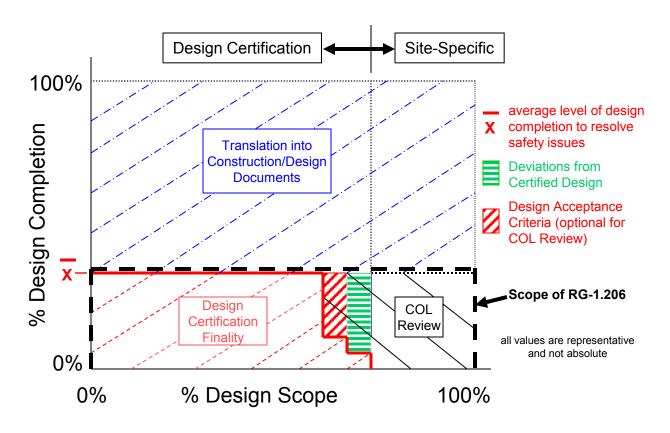


### Licensing under 10 CFR Part 50

- Lack of finality at construction permit stage
- Final safety decisions not made until plant is nearly complete and most costs expended
- Construction delay and rework because of design and regulatory changes
- Public participation difficult



### **Level of Detail**



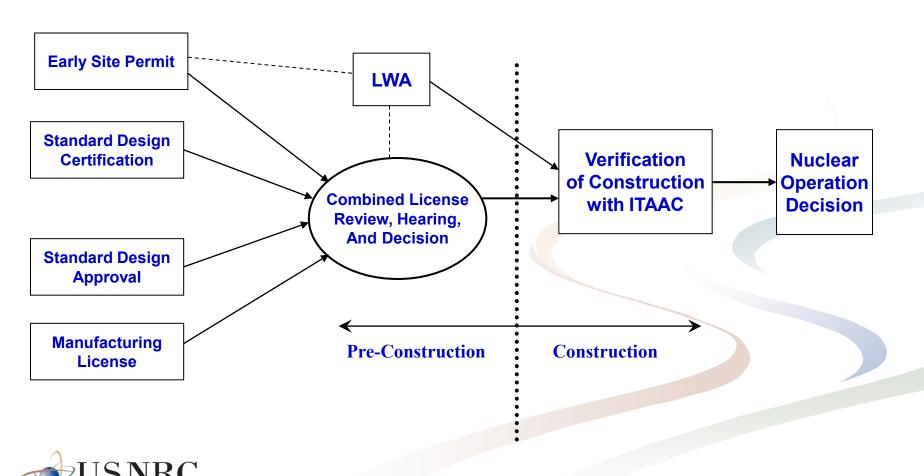
**Combined License Application Referencing a Certified Design** 

#### Licensing under 10 CFR Part 52

- Stable and predictable licensing process
- Resolves safety and environmental issues before authorizing construction
- Timely and meaningful public participation
- Standardization of nuclear plant designs
- Reduces financial risk to licensees (COL)



#### **Part 52 Licensing Process**



#### **Conclusions**

- CP/OL application requirements in 50.34 were not fully updated post-TMI
- Application guidance out-of-date (RG 1.70)
- Some modern requirements are not applicable, e.g. TMI, PRA, Severe Accidents
- Plant design achieves finality at OL
- Many licensing steps in the CP/OL process